

AMENDMENTS TO THE SPECIFICATION

Please replace paragraph [0026] with the following amended paragraph:

[0026] In one aspect, a substrate is provided wherein one of its surfaces has regions covered with a mask and regions that are uncovered or unmasked. The unmasked regions denote the areas targeted for the synthesis of nanotubes or nanostructures. Particles of catalysts, such as metals, are caused to be selectively deposited on the unmasked regions. Generally, a layer of metalorganic compound is deposited on the unmasked regions, and the organic component is removed, such as by oxidation, to give the catalytic metal particles at particular locations on the substrate. The substrate having catalyst particles formed on its surface is then exposed to a carbon precursor gas to give the single-walled carbon nanotubes and nanostructures. Thus, carbon nanotubes and nanostructures are produced at the locations of the catalyst particles by a chemical vapor deposition (CVD) process. A flow chart of the method is illustrated in Figure 1. In step 210, a masked substrate is provided; in step 220, a metalorganic layer is deposited; in step 230, the deposition mask is removed; in step 240, the metalorganic layer is oxidized; and in step 250, the one-dimensional carbon nanostructures are synthesized. The size and type of carbon nanostructures formed during the chemical vapor deposition can be controlled by controlling the size of the catalyst particles that are deposited on the unmasked surface of the substrate.